



## Oxford PECVD

### Responsible

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### System Description

Our "Oxford PECVD" is a Plasmalab 80Plus mixed frequency PECVD tool from Oxford for the Plasma Enhanced Chemical Vapor Deposition (PECVD) of low stress high density SiO<sub>2</sub>, SiN and SiON.

It is the old version of the [PlasmaPro 80 PECVD](#).

### Sample size:

Up to 100mm wafers.

### Materials restrictions:

Au free!

Please check the material and temperature compatibility with LNQ staff.

### Gases available:

SiH<sub>4</sub>, N<sub>2</sub>, O<sub>2</sub>, NH<sub>3</sub>, N<sub>2</sub>O, Ar, He.

### Substrate holder temperature:

20°C to 400°C, standard deposition processes at 300 °C

### Power supplies:

30/300 W 13.56 MHz solid state RF generator and 600W 90-460kHz LF generator

Low frequency LF5 – 500W RF power supply, 50 to 460 kHz in 100Hz steps.

High frequency HF10 – 1000W ICP65 source, Electrode size 240mm

*Check the short manual, process sheets and the [internal wiki page](#) for more details.*